

Oxidation Behavior of Mo-Si-W Ternary Alloys in the Temperature Range of 400°C-900°C

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Abstract:

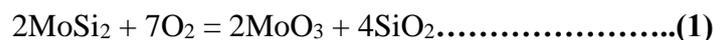
The intermetallic compound, MoSi₂ and ternary Mo-Si-W alloys - MoSi₂-25 wt% WSi₂ and MoSi₂-50 wt% WSi₂ were processed by reaction hot pressing at 1500°C. The microstructure of MoSi₂ with 25 and 50 wt% WSi₂ alloys showed (Mo,W)Si₂ phases, which were either rich in Mo or in W, as well as Mo₅Si₃ and W₅Si₃. Oxidation experiments were carried out in the temperature range of 400° C – 900° C for 24 hours in dry air, kinetic study was carried out by observing the change in mass at different intervals of time. The oxide scales in MoSi₂ were comprised of MoO₃, Mo₉O₂₆ and SiO₂. In addition to these scales WO₃ was observed in case of the MoSi₂-25 wt% WSi₂ and MoSi₂-50 wt% WSi₂ alloys. In MoSi₂-25 and 50 wt% WSi₂ alloys, the oxidation behavior was characterized chiefly by mass gain at temperatures less than 700°C and partial mass loss at higher temperatures. The gain in mass is more in the MoSi₂-50 wt% WSi₂ alloy, compared to the former, because of higher activity of W contributing to a larger volume fraction of WO₃ in scale. At higher temperatures, net mass loss was observed in the initial stages, because of the volatilization of MoO₃.

Keywords: Oxidation, MoSi₂, volatilization, rate constant

1. Introduction:-

MoSi₂ undergoes pesting, a phenomenon of accelerated oxidation induced disintegration, between 400°C and 600°C [1-3]. Pesting occurs because of the internal stress caused by volume expansion during selective oxidation at the grain boundaries, cracks and porosities. Intermetallics such as silicides, aluminides and beryllides suffer from the pesting phenomenon. The pest oxidation to stress-enhanced oxidation because of the high residual stress introduced via cooling anisotropic materials from the melt [4, 5]. The catastrophic nature of the pest oxidation was the result of preferential intergranular diffusion of a gaseous element (most probably oxygen or nitrogen) coupled with grain boundary embrittlement [6]. The oxidation of Mo and Si at the initial cracks with a large volume expansion induced the pesting of MoSi₂. However single-crystals

and crack-free polycrystalline MoSi_2 prepared by hot isostatic pressing (HIP) did not disintegrate [7, 8]. The former [7] suggested that the susceptibility of near-stoichiometric MoSi_2 to pest disintegration increased with decreasing density; while the latter proposed that pest did not occur in dense (>95%) MoSi_2 for exposure times up to 688 h at 400-600⁰C [9]. From thermodynamic considerations [10], it follows that Si in MoSi_2 should be selectively oxidized to SiO_2 because its affinity for oxygen is much greater than that of Mo. The mass gain followed by large mass loss during the initial heating to the test temperature can be attributed to oxidation of silicon and molybdenum, followed by sublimation of MoO_3 . It also suggested that plate-like MoO_3 grows by vapor deposition. The amorphous Mo-Si-O and Mo-Si-W-O oxides, which were formed during initial stages of this study, have composition of metal elements close to that in the initial intermetallics.



The calculated volume change involved in reaction (1) is about 212 vol% [1].

2. Experimental Procedure:-

For MoSi_2 , Mo and Si, and for MoSi_2 -25 and 50wt% WSi_2 alloys, Mo, W and Si powders were mixed in stoichiometric ratios in pots in a planetary ball mill. The powder mixtures were subsequently reaction hot pressed at 1500⁰C in argon atmosphere with pressure of 26 MPa for 1 hour at the DMRL, Hyderabad. These hot pressed plates were electro-discharge machined (EDM) to bar type specimens of rectangular cross-section with dimensions, 12 mm x 6 mm x 4.5 mm. The specimen bars were first polished and cleaned and then subsequently the samples were suspended inside the quartz tube chamber of the oxidation furnace, using a nichrome wire, which again is hung from the pan of the weight balance kept on a platform above the furnace. The oxidations of the samples were carried out at the temperature 400 – 900⁰C.

2.1. Characterization:-

The samples were studied using bright field and polarized light optical microscopy to study the distribution of porosities and measure grain size, XRD was performed to identify the phases present. Subsequently, the microstructures were observed using secondary electron (SE) and backscattered electron imaging modes on SEM and EPMA.

3. Results and Discussions:-

3.1. MoSi_2 .

The XRD patterns, using Cu K α radiation, is shown in fig.3.1.1 depicted the XRD pattern of MoSi_2 alloy exposed at 700⁰C for 24 hrs shows the peaks of MoO_3 , Mo_9O_{26} and SiO_2 and (Mo, W) Si_2 originating from the alloy substrate. The SEM images of MoSi_2 alloy exposed at 700⁰C were shown in fig.3.1.2.

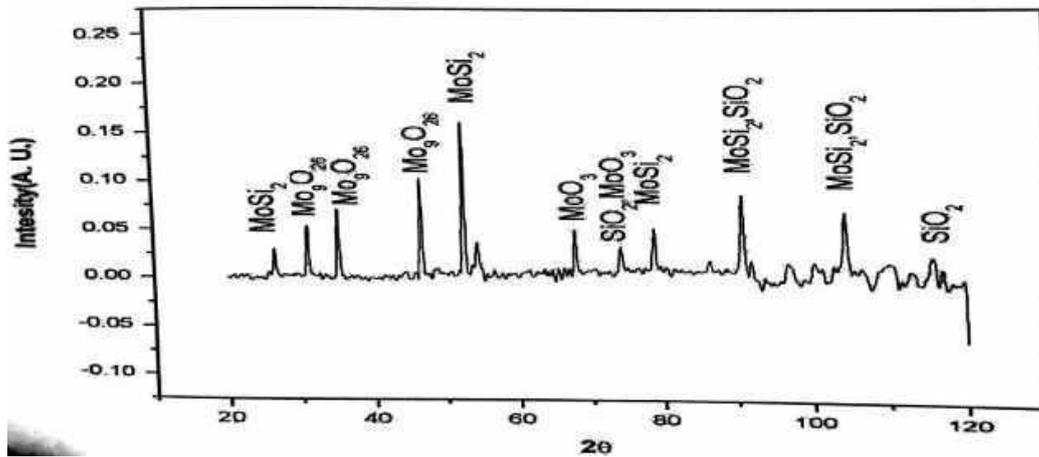


Fig. 3.1.1 XRD pattern of MoSi₂ alloy exposed at temperature of 700°C.

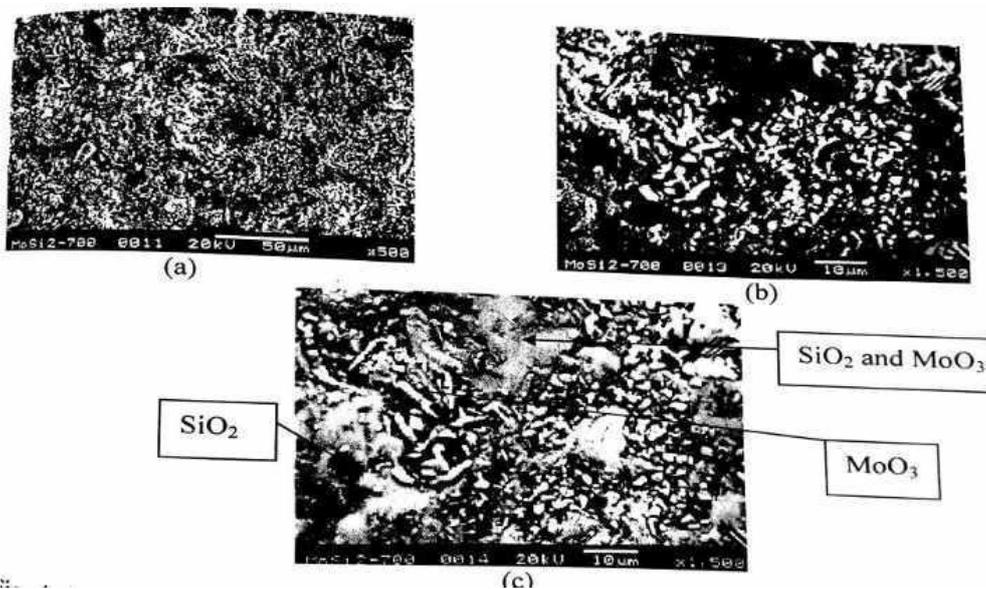


Fig. 3.1.2 SEM micrographs of MoSi₂ alloy exposed at 700°C for 24 hrs (a) SE mode, (b) SE mode at higher magnification and (c) BSE mode.

3.2. MoSi₂-25wt%WSi₂ alloy.

The XRD pattern of the alloy MoSi₂-25wt%WSi₂ as shown in fig.3.2.1(a) shows prior to oxidation of alloy and fig.3.2.1 (b) shows after exposed at 700°C for 24 hrs. From fig.3.2.1 displays that the peaks of MoO₃, Mo₉O₂₆, WO₃, SiO₂ and (Mo, W)Si₂. The shift in peak position of (Mo, W)Si₂ with respect to that of MoSi₂ is found to be negligible. Fig.3.2.2 represents a polarized light optical micrograph before oxidation showing the grain size to be around 12 μm where as the fig.3.2.3 shows SE and BSE images of alloy MoSi₂-25wt%WSi₂ at different magnifications. The EPMA (WDS)

analysis have revealed the brightest phase to be riched in W (atomic number=74) with concentration in the range of 16-26 at%. The matrix, which appears to be dark compared to the W-rich phase, is enriched in Mo (atomic number=42) having concentration of W being about 5-8 at%. The phase appearing dark and globular is indentified to be SiO₂.

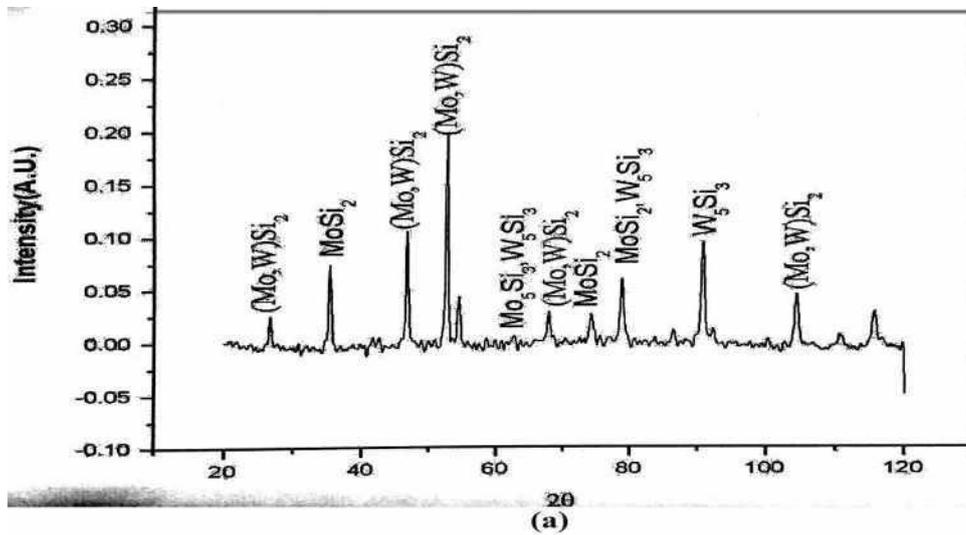


Fig. 3.2.1(a) XRD pattern of MoSi₂-25 wt% WSi₂ alloy before oxidation.

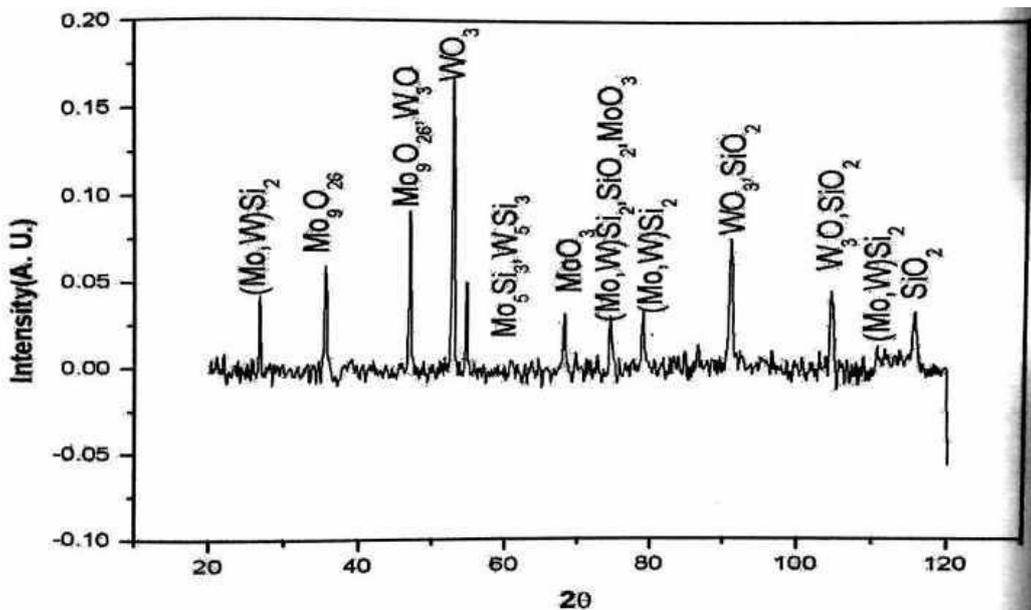


Fig. 3.2.1(b) XRD pattern of MoSi₂-25 wt% WSi₂ alloy after oxidation.

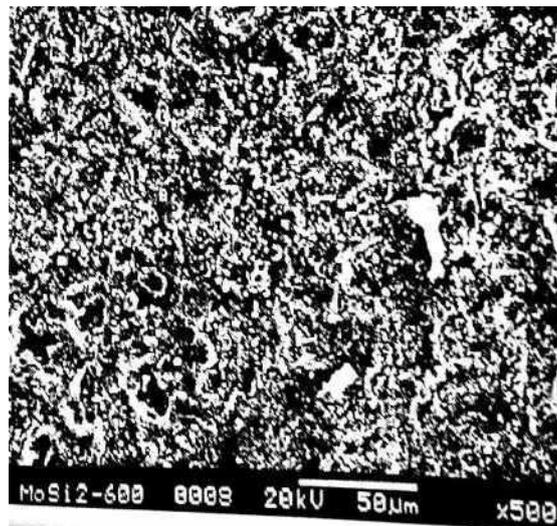


Fig. 3.2.2 Polarized light optical micrograph of MoSi₂-25 wt% WSi₂.

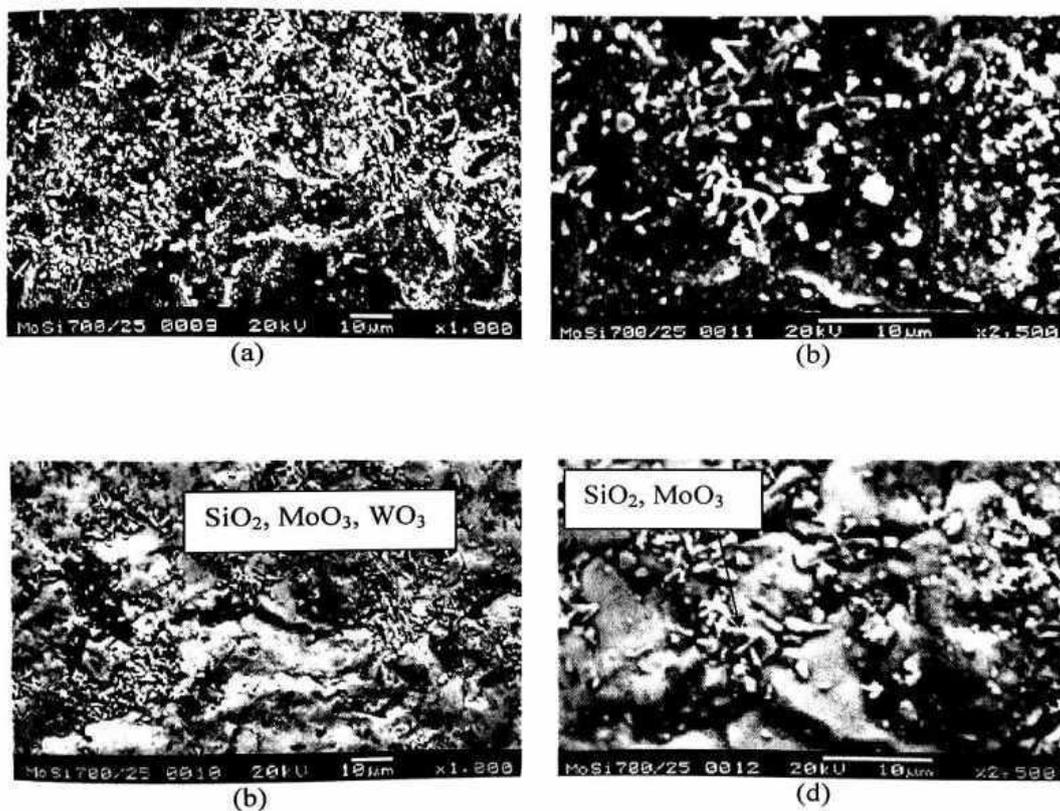


Fig. 3.2.3 SEM micrographs of MoSi₂-25 wt% WSi₂ alloy exposed at 700°C for 24 hrs (a) SE mode, (b) SE mode at higher magnification and (c) and (d) are BSE images at lower and higher magnification.

3.3. MoSi₂-50wt% WSi₂ alloy.

Chemical composition obtained from EDAX analysis of MoSi₂-50wt% WSi₂ alloy is shown in table-1. Fig.3.3.1 shows the XRD pattern of MoSi₂-50wt% WSi₂ alloy exposed at 700°C respectively. These XRD pattern indicates the peaks of MoSi₂, W₅Si₃, MoO₃ and WO₃ in addition to (Mo, W)Si. In fig. 3.3.2 shown the WDS analysis have revealed the W-rich region contain 28 at% W, while W-lean regions about 10 at%.

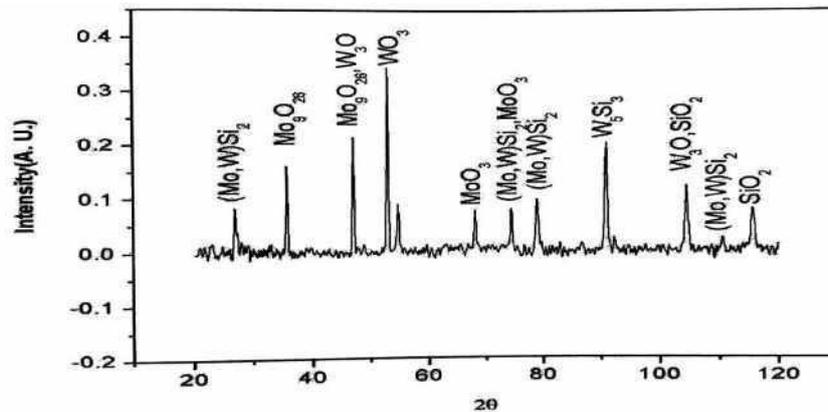


Fig. 3.3.1 XRD pattern of MoSi₂-50 wt% WSi₂ alloy after oxidation.

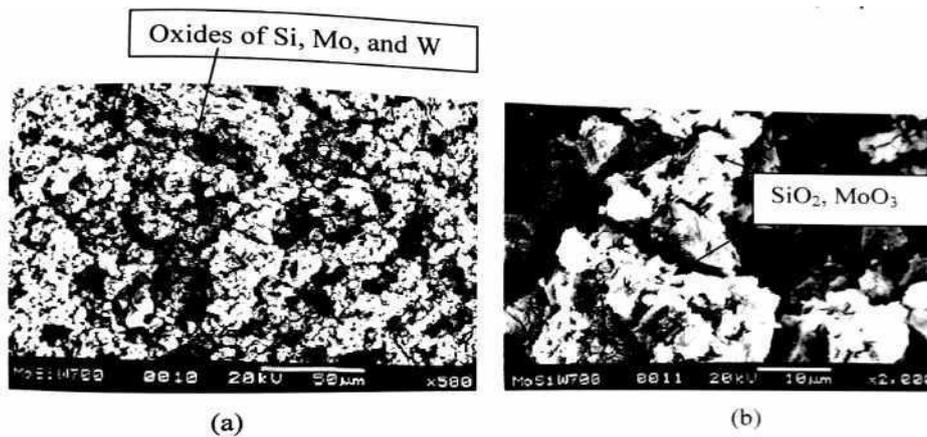


Fig. 3.3.2 (a) and (b) SEM micrograph of MoSi₂-50 wt% WSi₂ exposed to 700°C at different magnifications.

4. Oxidation Kinetics of three alloys.

Fig.4 shows the plots describing the kinetics of oxidation of MoSi₂, MoSi₂-25 wt.% WSi₂ and MoSi₂-50 wt.% WSi₂ alloys exposed at 700°C in dry air for 24 h. Oxidation at all temperatures are characterized by a rapid rate of gain in mass during the first two hours, followed by a reduced rate for all alloys. The rate of mass gain is least in MoSi₂-25 wt.% WSi₂ alloy followed by MoSi₂-50 wt.% WSi₂ alloy and MoSi₂.

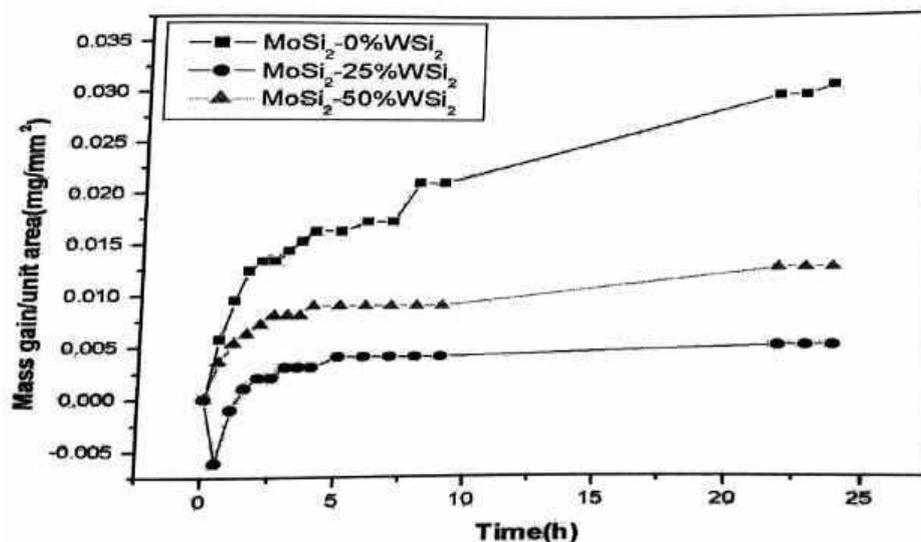


Fig.4. Plots of oxidation kinetics of MoSi₂, MoSi₂-25 wt.% WSi₂ and MoSi₂-50 wt.% WSi₂ alloys exposed at 700°C for 24 h.

XRD analysis has confirmed the oxidation products to chiefly consist of MoO₃, WO₃ and SiO₂ phases. Below the oxidation temperature of 700°C the mass gain is due to the formation of four oxides i.e. MoO₃, WO₃, SiO₂ and MoO₃ where as at above 700°C, MoO₃ is volatile and oxidation kinetics involves partial loss in mass.

5. Conclusions:-

- The microstructures of MoSi₂-25 wt.% WSi₂ and MoSi₂-50 wt.% WSi₂ alloys showed primarily (Mo, W)Si₂ phase, as well as Mo₅Si₃ and W₅Si₃. Dispersed particles of SiO₂ would observe both in the MoSi₂ and Mo-Si-W alloys.
- Oxidation behaviour of MoSi₂, MoSi₂-25 wt.% WSi₂ and MoSi₂-50 wt.% WSi₂ alloys in the temperature range of 400°C – 900°C in dry air demonstrated two principal time regimes. The initial exposure period exhibited a rapid rate of reaction while the second stage usually showed reduced rate of oxidation suggesting the formation of protective scales.
- The oxide scale chiefly consisted of SiO₂, MoO₃ and Mo₉O₂₆ in MoSi₂ alloy and SiO₂, MoO₃, WO₃ and Mo₉O₂₆ oxides are existed in MoSi₂-25 wt.% WSi₂ and MoSi₂-50 wt.% WSi₂ alloys. MoO₃ could not detect at 800°C and 900°C due to its volatilization.

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